PLASMA PROCESSING APPARATUS AND SUBSTRATE PROCESSING APPARATUS

Abstract

To provide a technique that can recover a substance flowing out of a substrate processing space. A plasma processing apparatus includes a chamber having a plasma processing space; and a plasma viewport attached to the chamber, in which the plasma viewport includes: a first window; a second window placed between the first window and the plasma processing space; a third window placed between the first window and the second window; and a lattice structure body placed between the second window and the third window.

Fig. 3